

Fig. 1

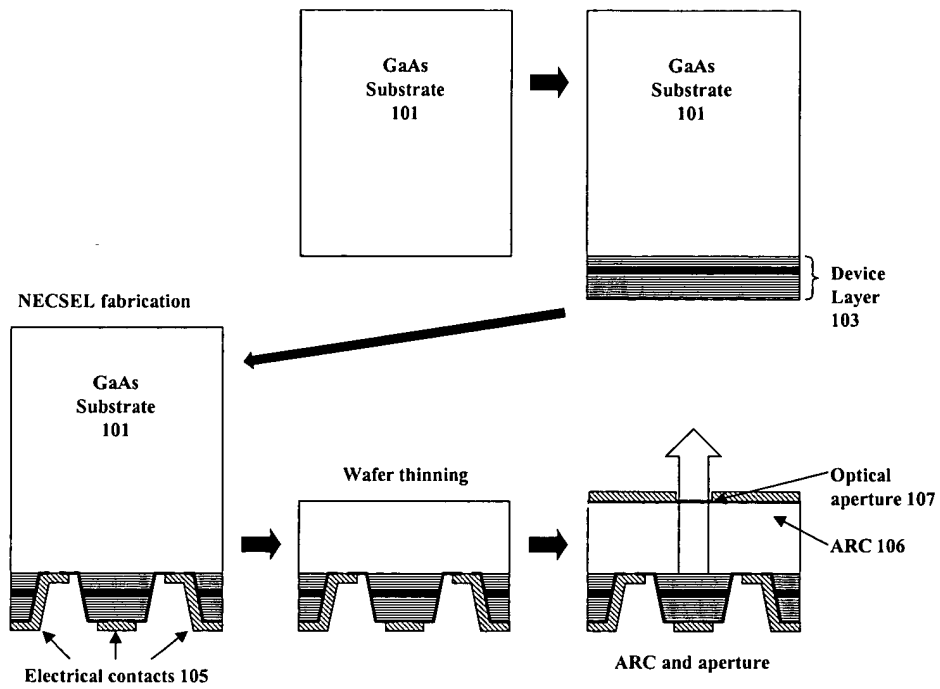


Fig 2

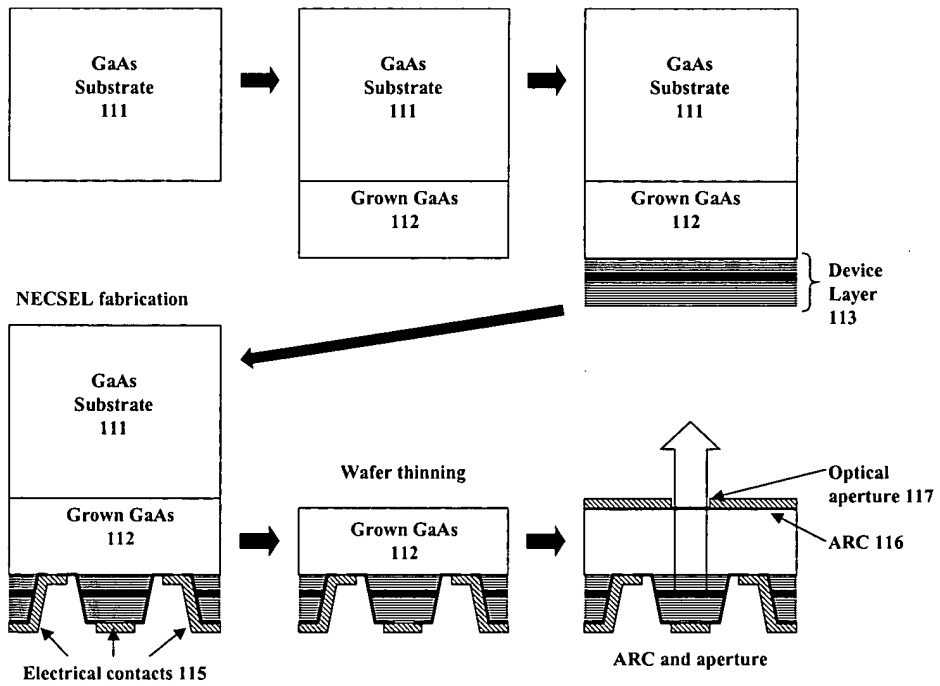


Fig 3a

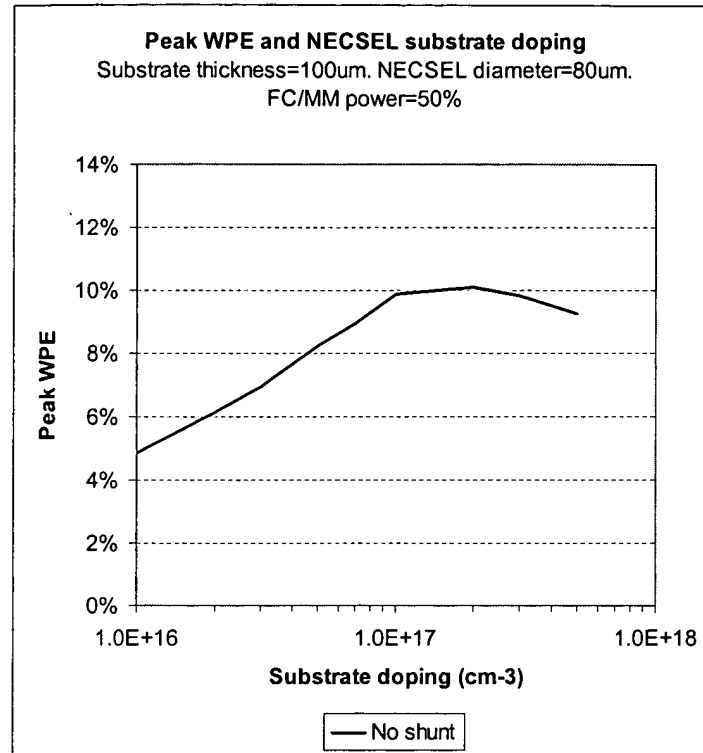


Fig 3b

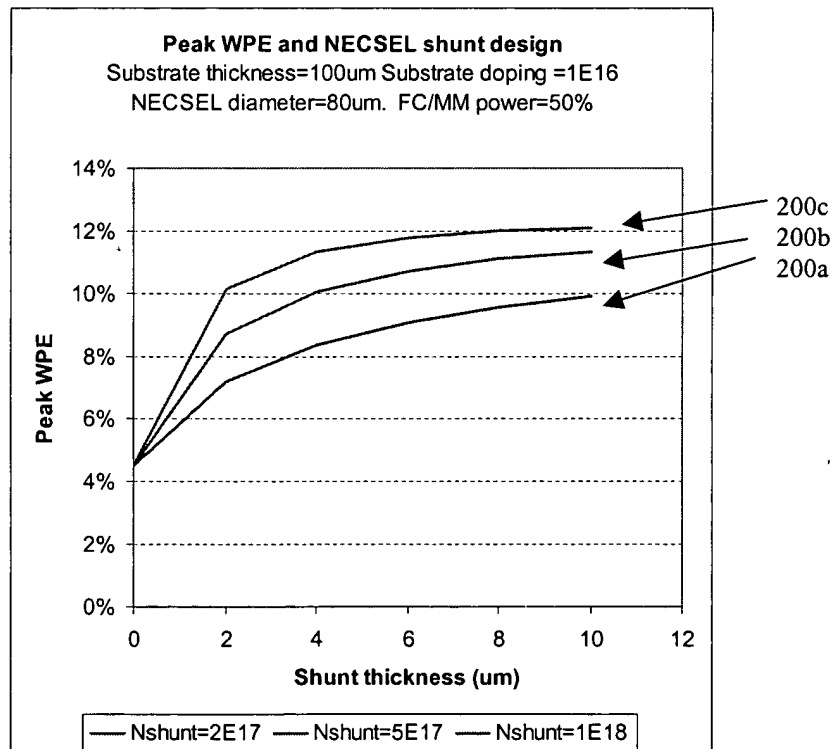


Fig. 4

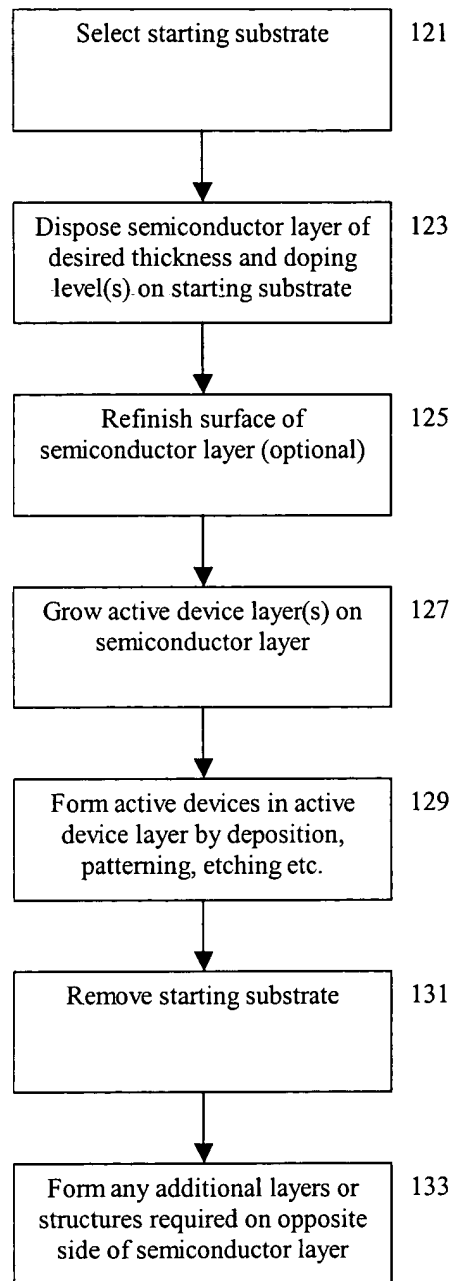
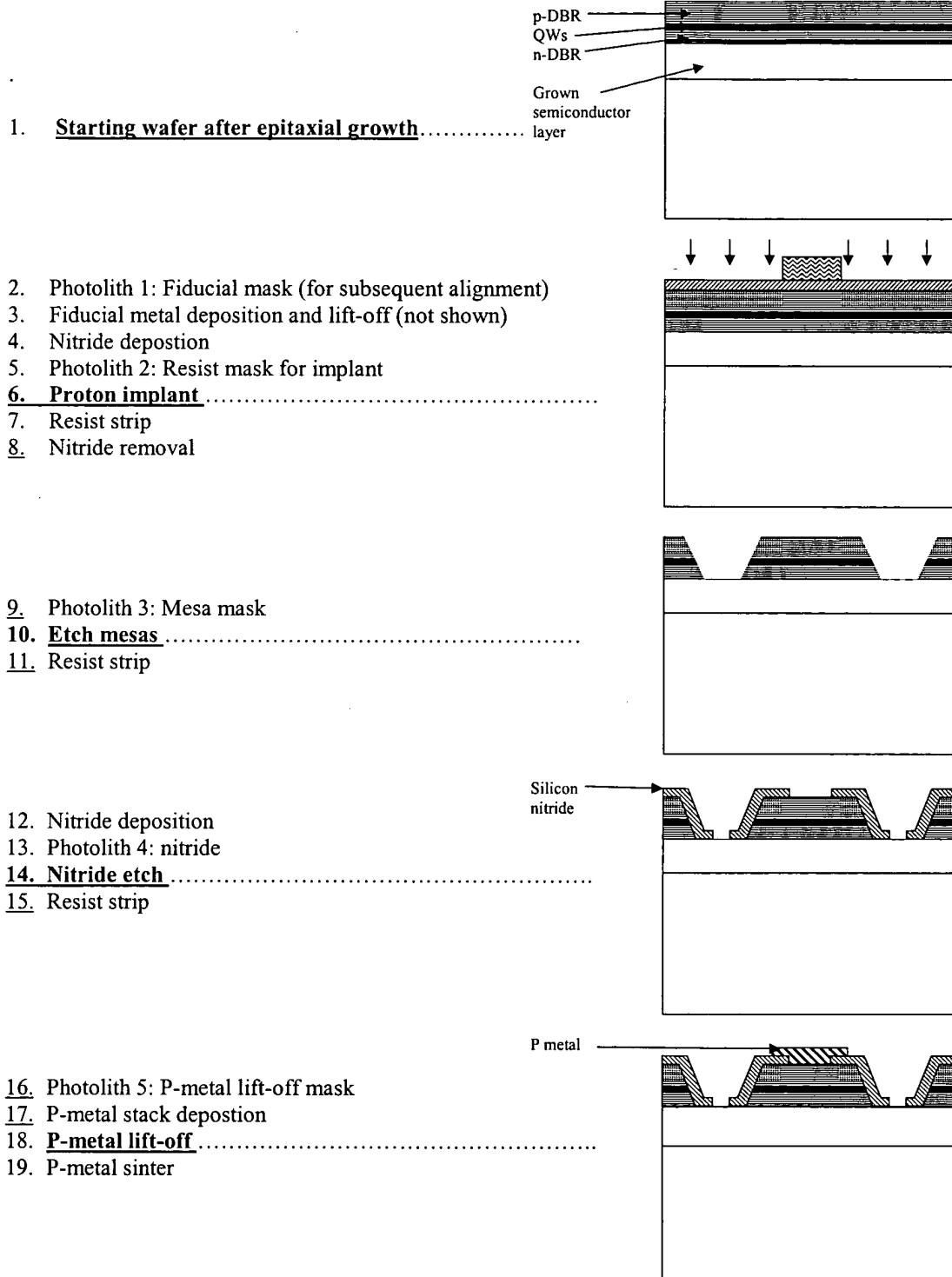


Fig 5.

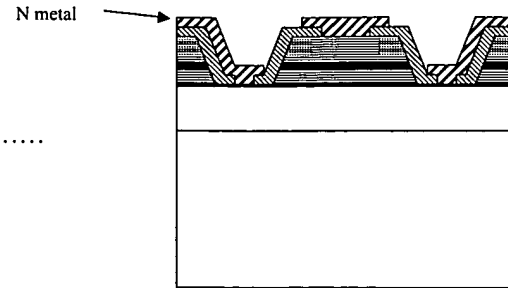


20. Photolith 6: N-metal lift-off mask

21. N-metal stack deposition

22. **N-metal lift-off**

23. N-metal sinter

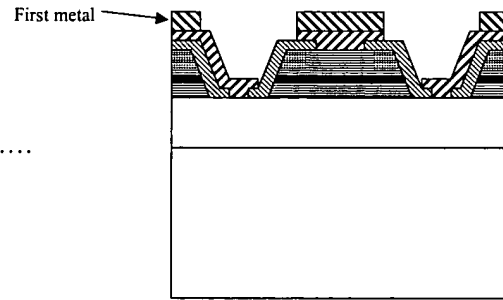


24. Photolith 7: First metal lift-off mask

25. First metal deposition

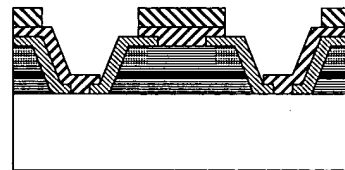
26. **First metal lift-off**

27. On-wafer test

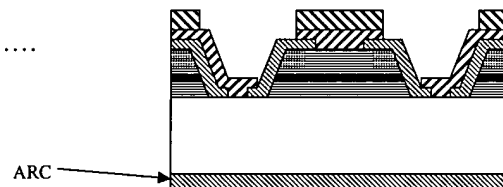


28. Wafer mount (epi side down) on sapphire substrate.

29. **Wafer thinning (lap and polish)**



30. **Anti-reflection coating (ARC) deposition**



31. Photolith 8: Aperture metal lift-off mask

32. Aperture metal deposition

33. **Aperture metal lift-off**

34. De-mount from sapphire substrate

35. Scribe and break

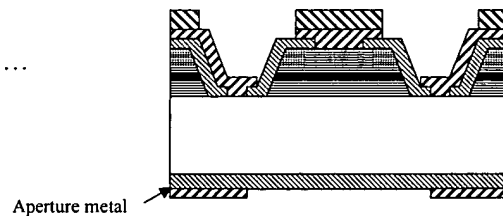


Fig 6

